

Terahertz technologies have gained a substantial interest due to their potential applications in different sectors such as security, quality control, information and communications, biology and medical sciences, and others [1]. However, the technology for generating and manipulating terahertz radiation is still in its infancy. The use of graphene-based materials has already been proposed [2, 3]. Our goal is to fabricate metasurfaces based on **multilayer graphene (MLG)** films on flexible substrates for manipulating terahertz radiation. This includes developing a production method for multilayer graphene films of controlled thickness, optimisation of multilayer graphene film transfer onto target substrates and engineering metasurfaces by means of photolithography.

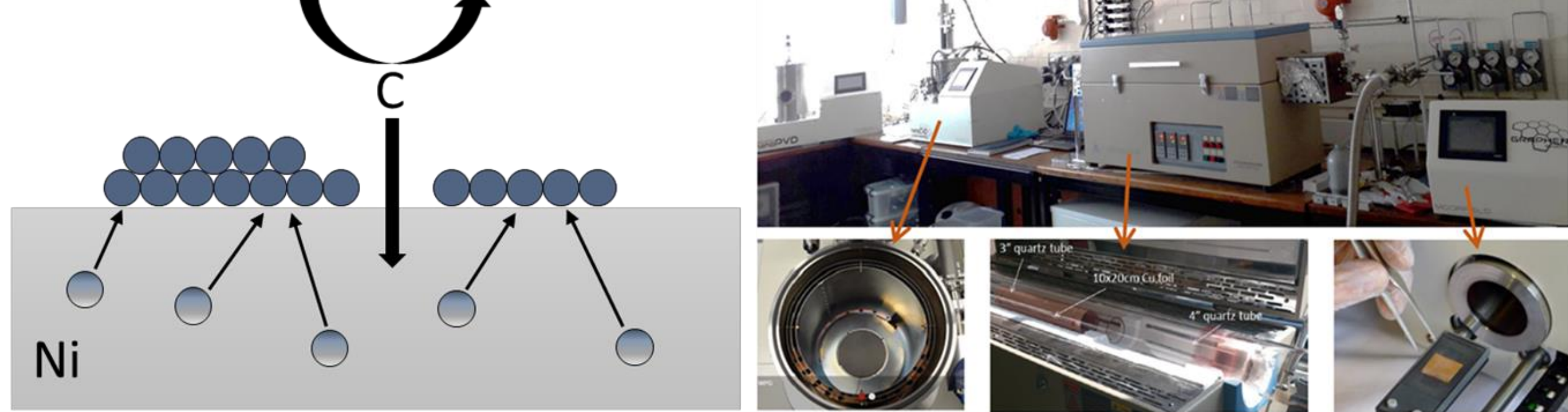
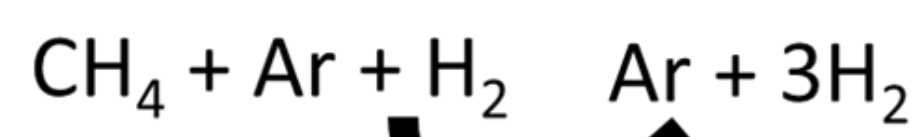
GROWTH

Chemical Vapour Deposition (CVD) + nickel catalyst

Large-area and high-quality MLG

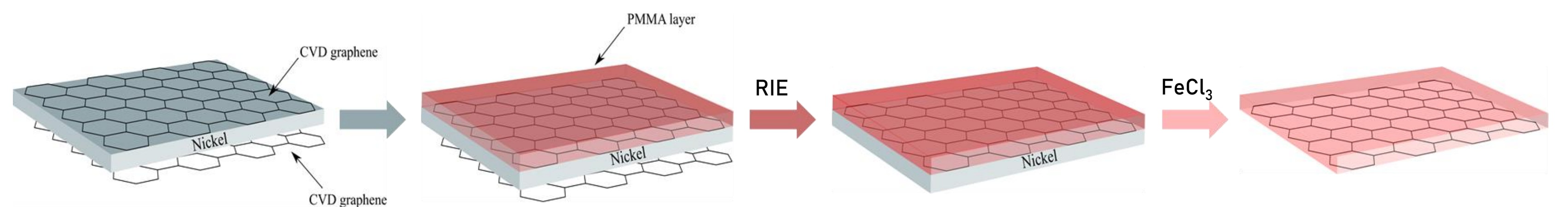
Controlling the number of graphene layers:

- Substrate thickness
- Pressure (APCVD, LPCVD)
- Temperature (850-1050 °C)
- Gas flow rate
- Residence time of the carbon source
- Cooling rate

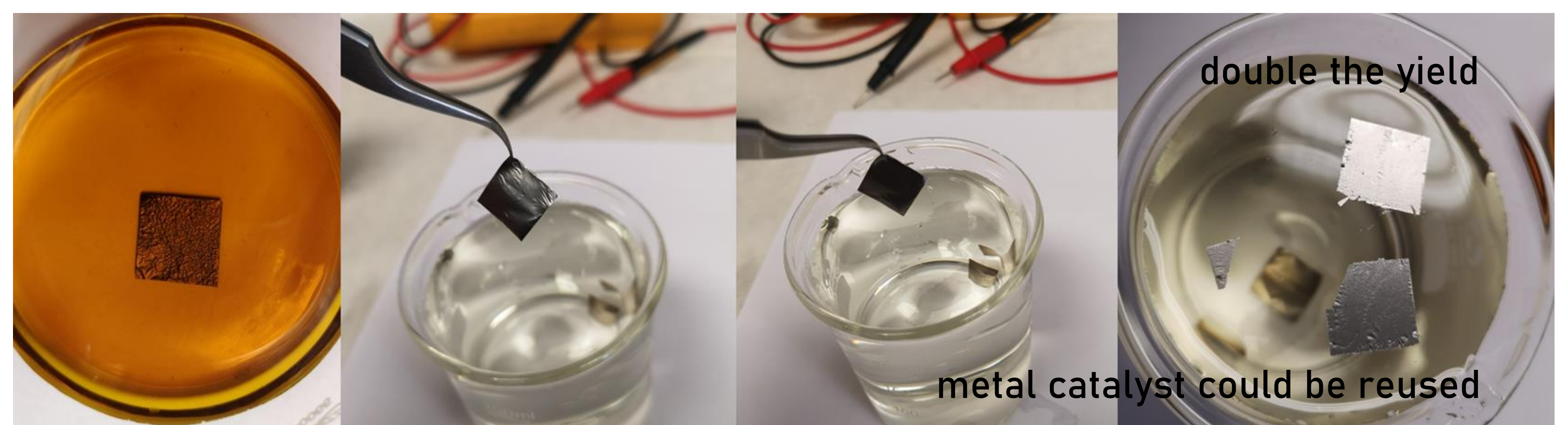
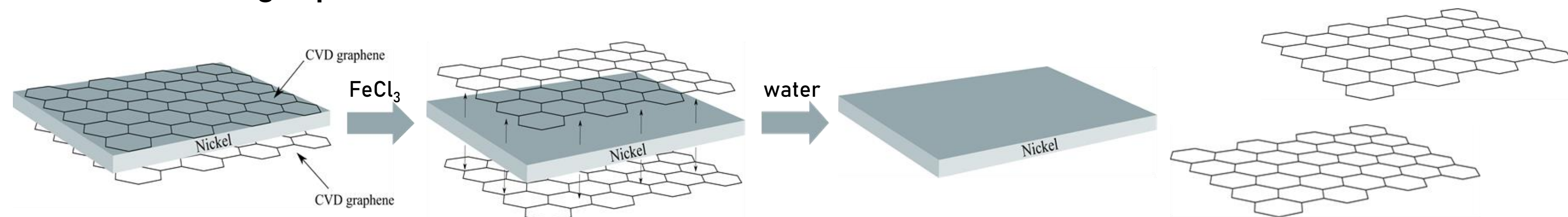


TRANSFER

Typical wet graphene film transfer



Modified wet graphene film transfer



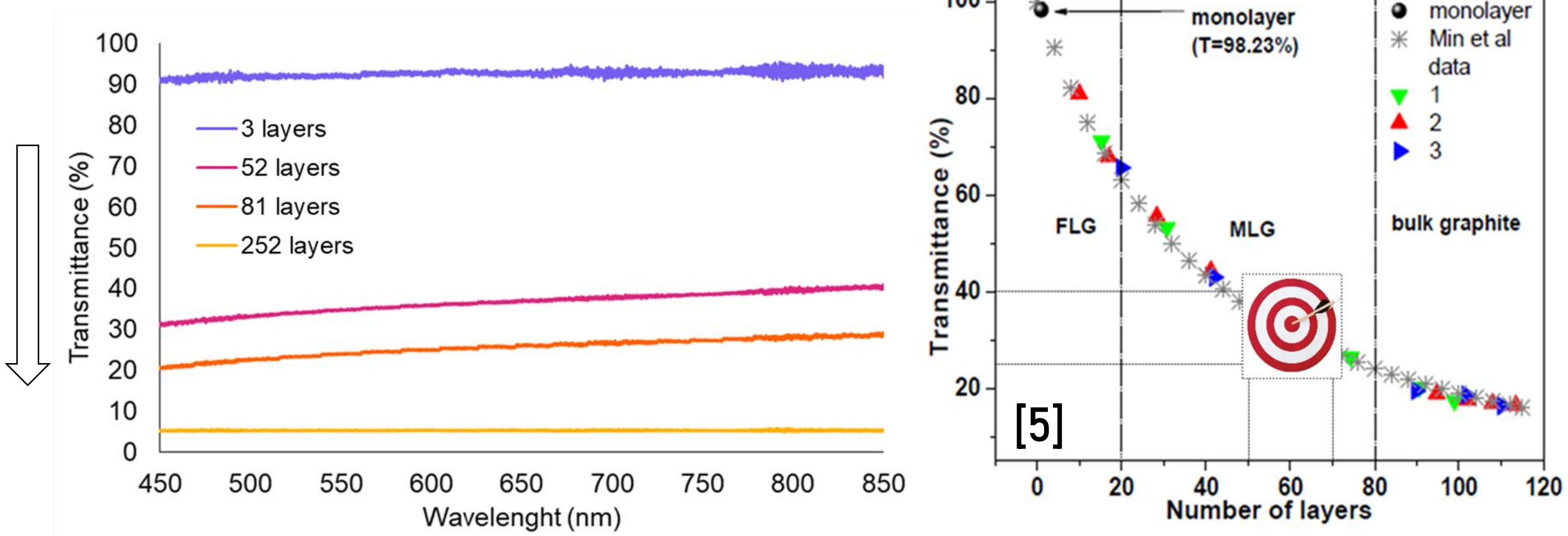
OPTICAL TRANSMITTANCE

For MLG the optical transmission is directly dependent on the optical conductance of the graphene stack and the optical transmittance [4].

$$T(\omega) = (1 + f(\omega)\pi\alpha N/2)^{-2}$$

$$1.13 \text{ at } 550 \text{ nm} \quad \rightarrow \quad e^2/hc \approx 1/137$$

Obtained optical transmittance data:

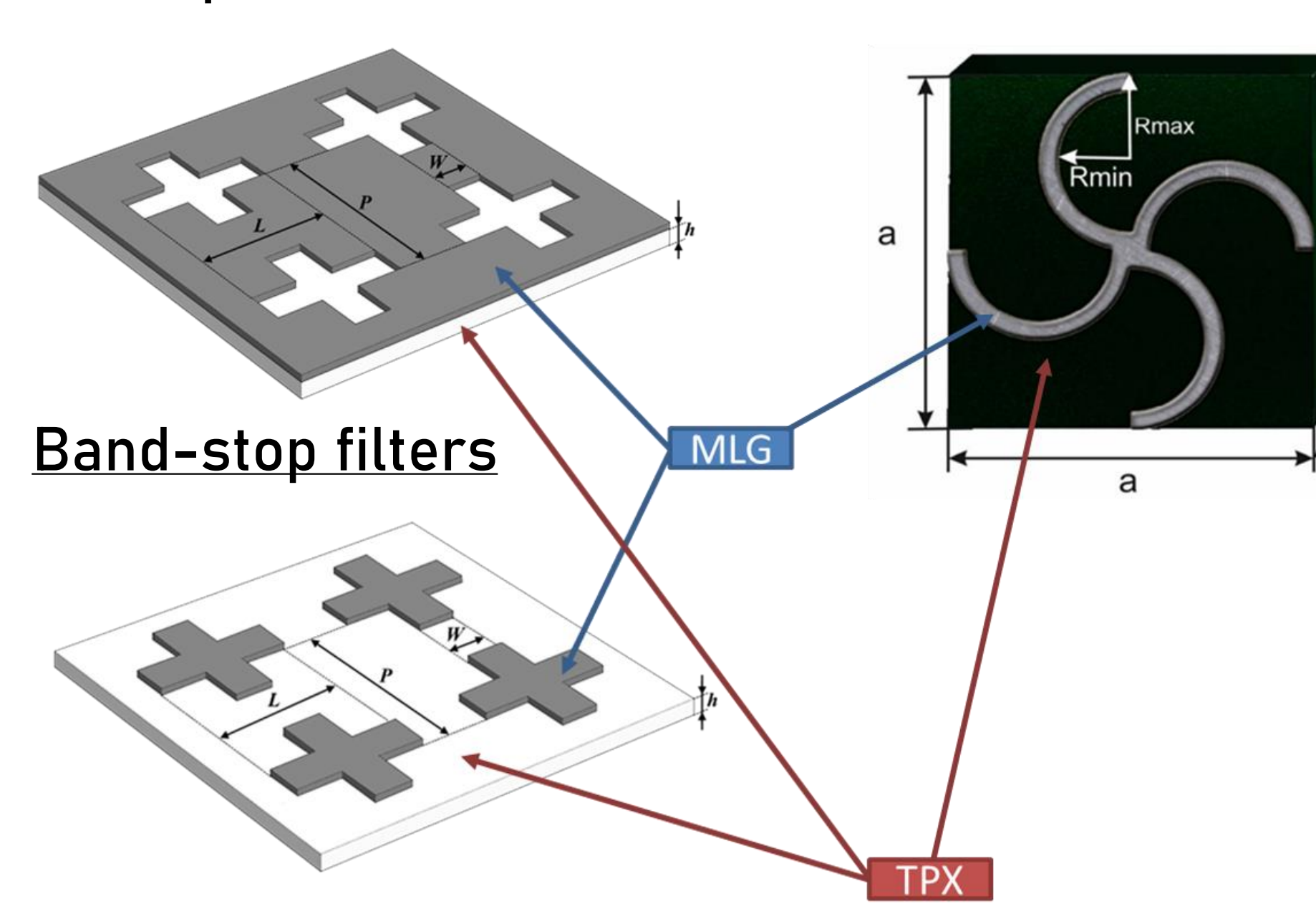


TERAHERTZ METASURFACES

The interaction between terahertz waves and MLG could be further enhanced by engineering periodic subwavelength sized patterns – metasurfaces [6].

Band-pass filters

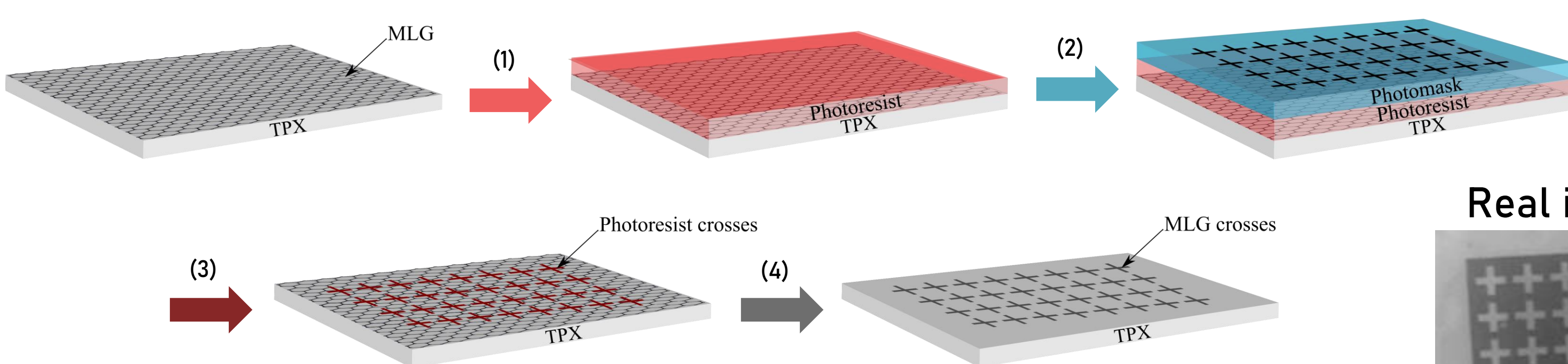
Chiral metasurfaces



Resonance frequencies 100-950 GHz;
Band-pass range 40 GHz

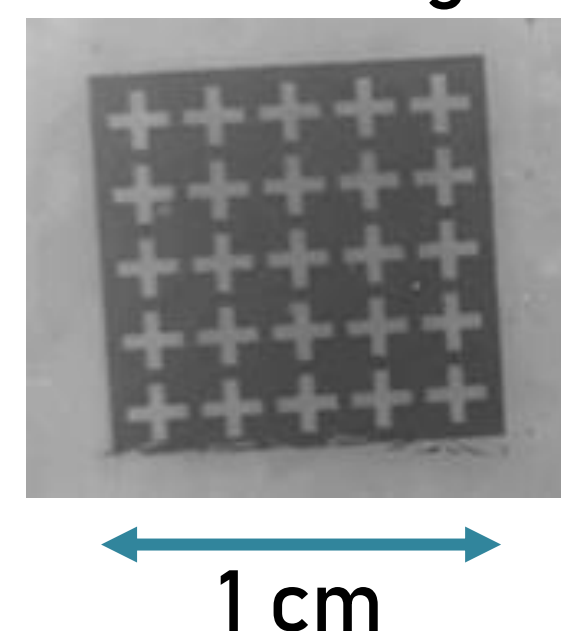
- TPX® – polymethylpentene:
- Optically transparent in UV, visible and THz ranges
 - Heat resistant
 - Chemical resistant
 - Flexible

FABRICATION



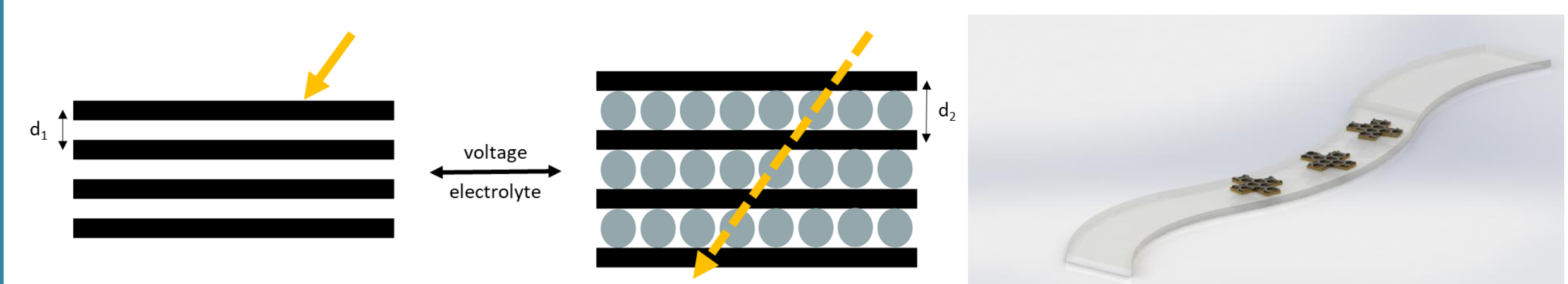
Photolithography: (1) spin coat photoresist, (2) apply photomask, (3) expose to UV light and develop a photoresist pattern, (4) etch the unprotected MLG with Ar/O₂ plasma to produce a desired MLG pattern.

Real image



FUTURE WORK

- Fabrication optimisation and testing of MLG-based metasurfaces for biophotonics applications
- Fabrication of MLG-based optical modulators with switchable transparency in THz range
- Textile substrates with graphene metasurfaces for wearable THz communication applications



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- [4] Shou-En Zhu et al., *EPL*, 2014, 108, 17007.
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- [6] S. Ke et al., *Opt. Express*, 2015, 23 (7), 8888-8900.

Acknowledgments

EPSRC Centre for Doctoral Training in Electromagnetic Metamaterials (EP/L015331/1), EP/S019855/1, H2020-MSCA-2015-704963, and the government of the Russian Federation (Grant 08-08).